

Electronic Supplementary Information (ESI)

Highly Active and Stable Nickel-Molybdenum Nitride ($\text{Ni}_2\text{Mo}_3\text{N}$) Electrocatalyst for Hydrogen Evolution

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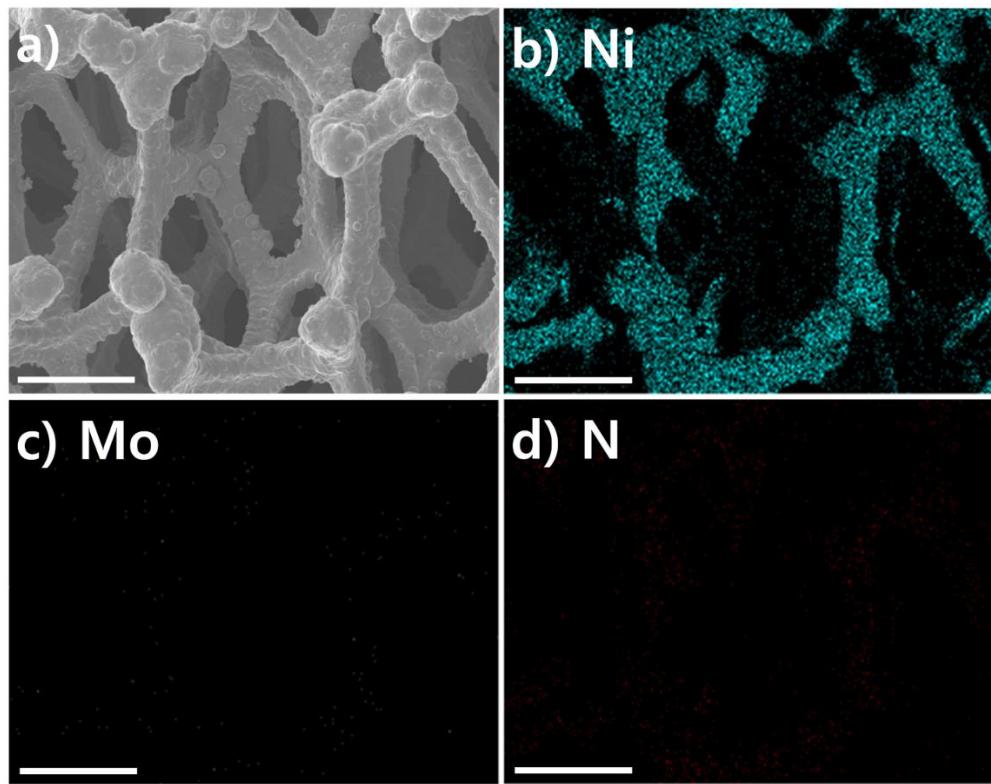


Fig. S1. SEM-EDS elemental mapping images for pristine Ni foam (scale bar = 300 μ m).

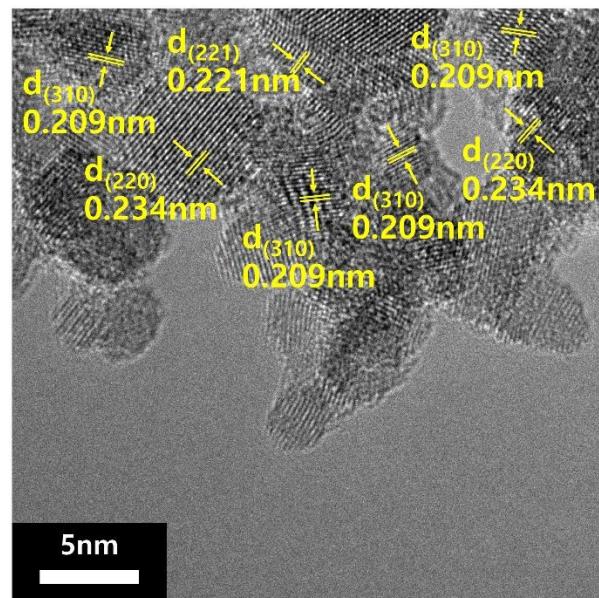


Fig. S2. HRTEM image of $\text{Ni}_2\text{Mo}_3\text{N}/\text{NF}$.

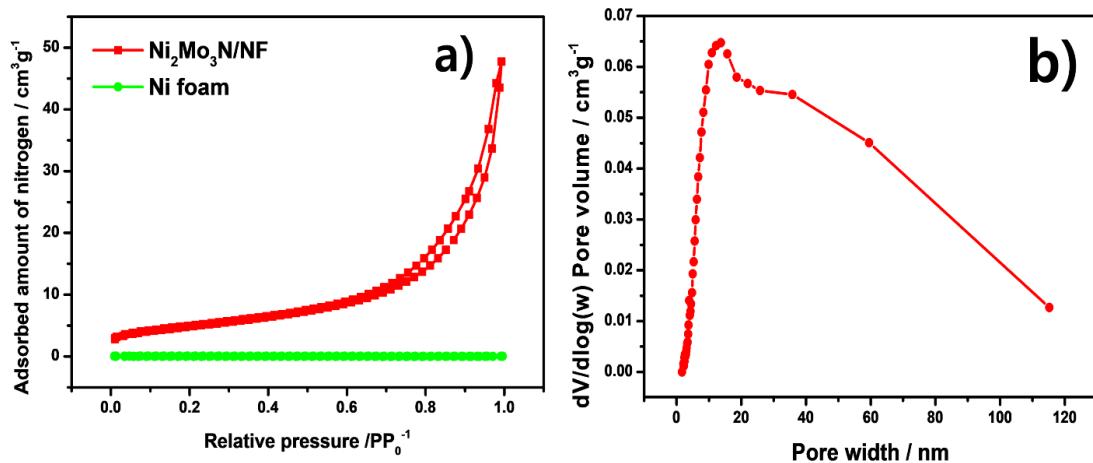


Fig. S3. a) N₂ adsorption-desorption isotherms and b) pore size distribution plot of Ni₂Mo₃N/NF.

N₂ isotherm of pristine Ni foam was added in a) for comparison.

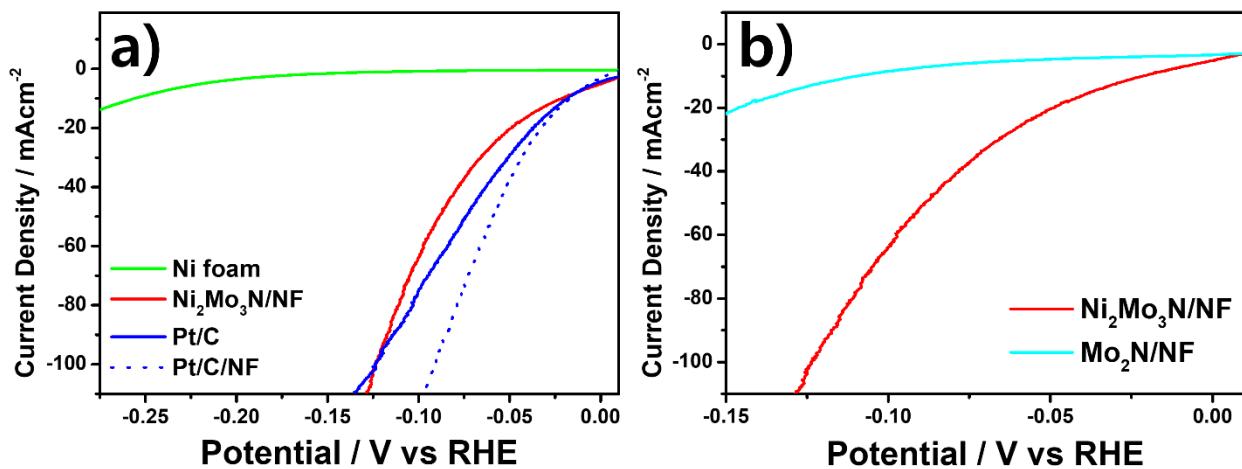


Fig. S4. Electrochemical polarization curves for the prepared catalysts a) including Pt/C/NF and b) including Mo₂N/NF.

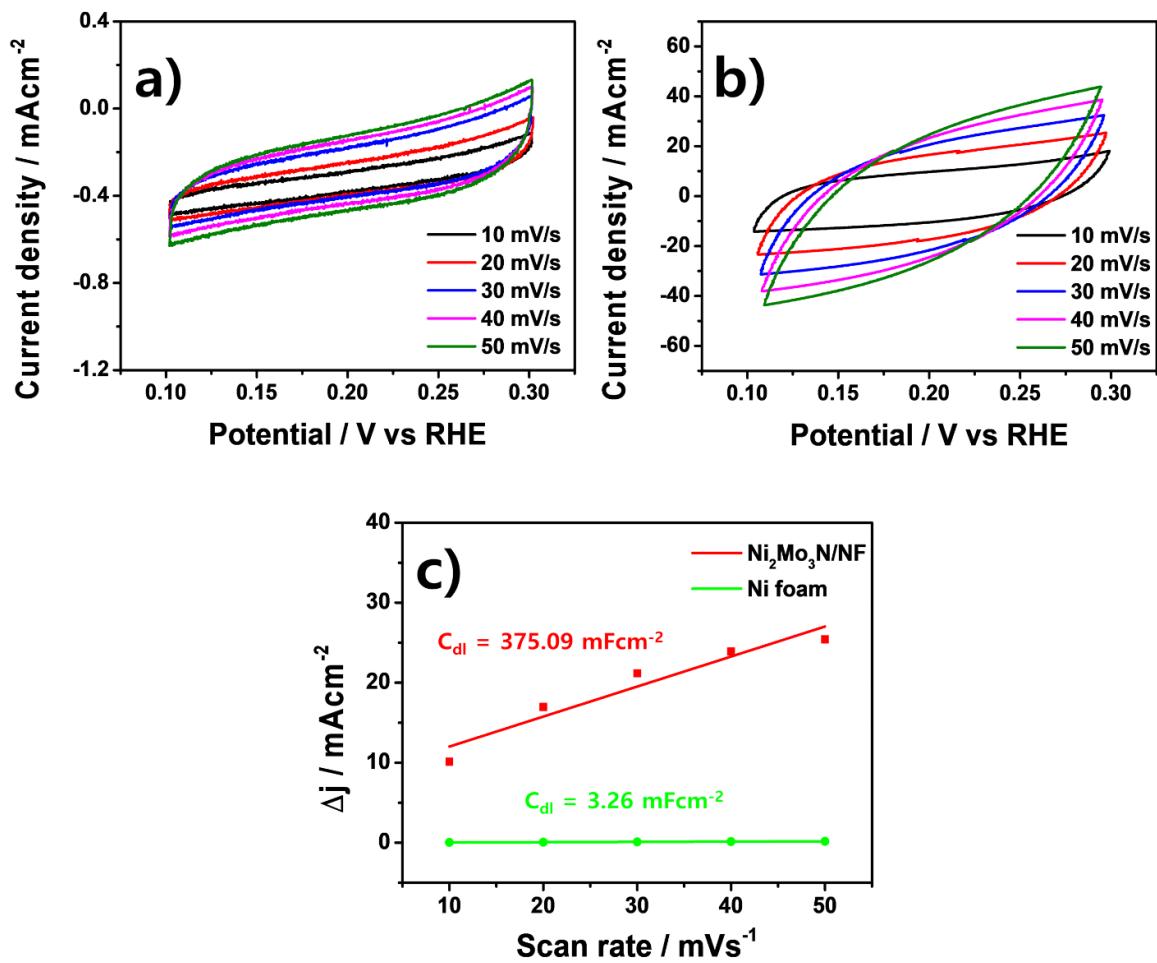


Fig. S5. Cyclic voltammograms of a) pristine Ni foam and b) Ni₂Mo₃N/NF at different scan rates in 1 M KOH solution. c) The corresponding current density versus scan rate plots showing C_{dl} values for pristine Ni foam and Ni₂Mo₃N/NF.

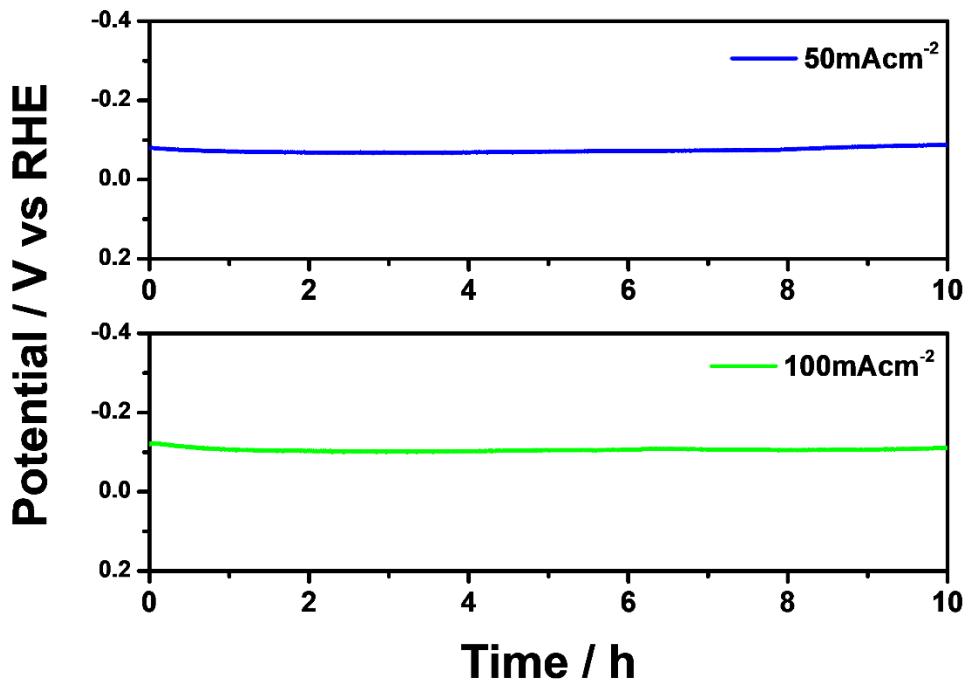


Fig. S6. Chronopotentiometry curves of $\text{Ni}_2\text{Mo}_3\text{N}/\text{NF}$ at 50 and 100 mA cm^{-2} for 10 h.

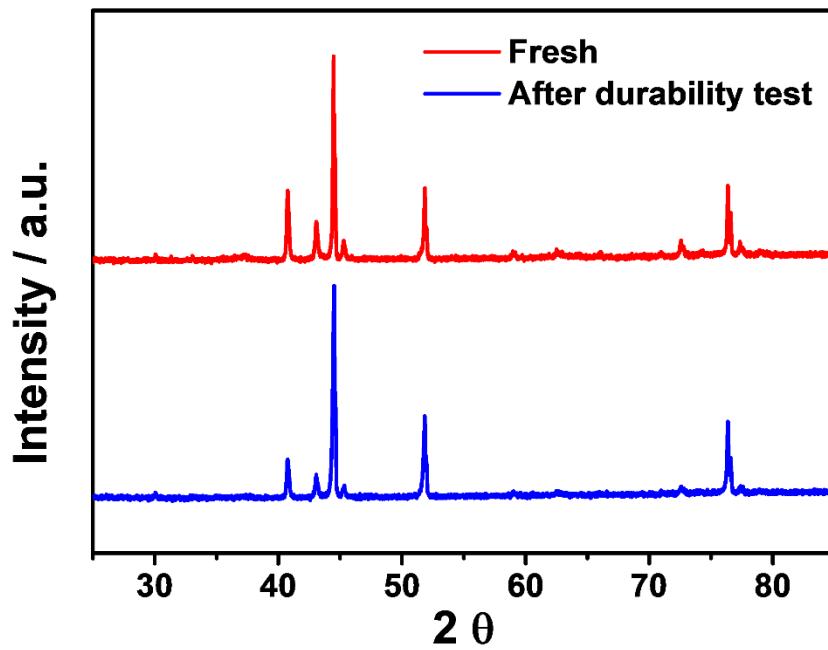


Fig. S7. XRD patterns of $\text{Ni}_2\text{Mo}_3\text{N}/\text{NF}$ fresh and after durability tests.

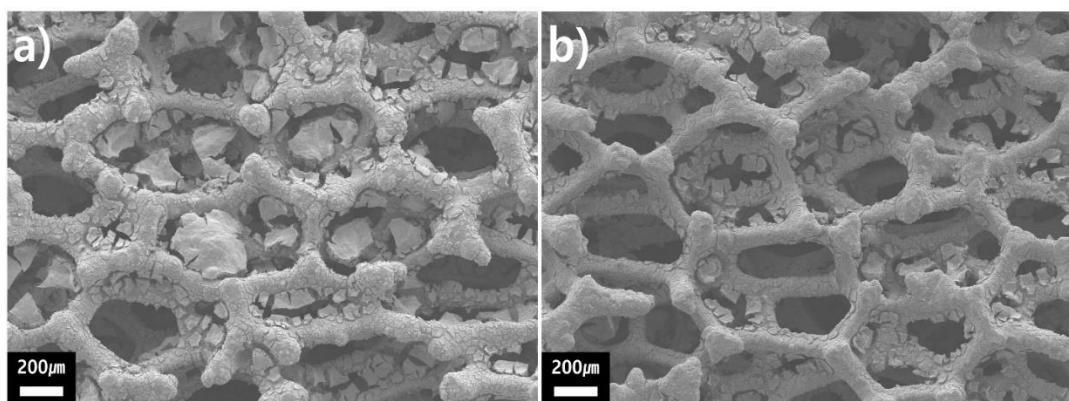


Fig. S8. SEM images of Ni₂Mo₃N/NF a) before and b) after durability tests.

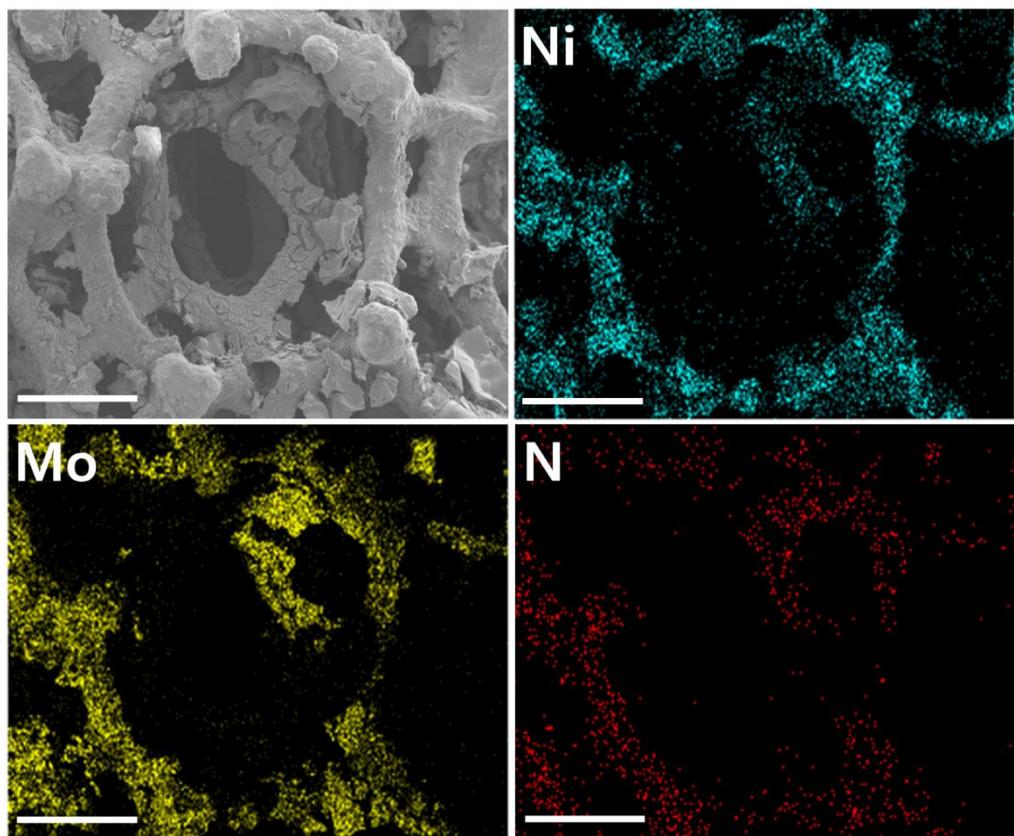


Fig. S9. EDS elemental mapping images of Ni₂Mo₃N/NF after durability tests (scale bar = 300 μm).

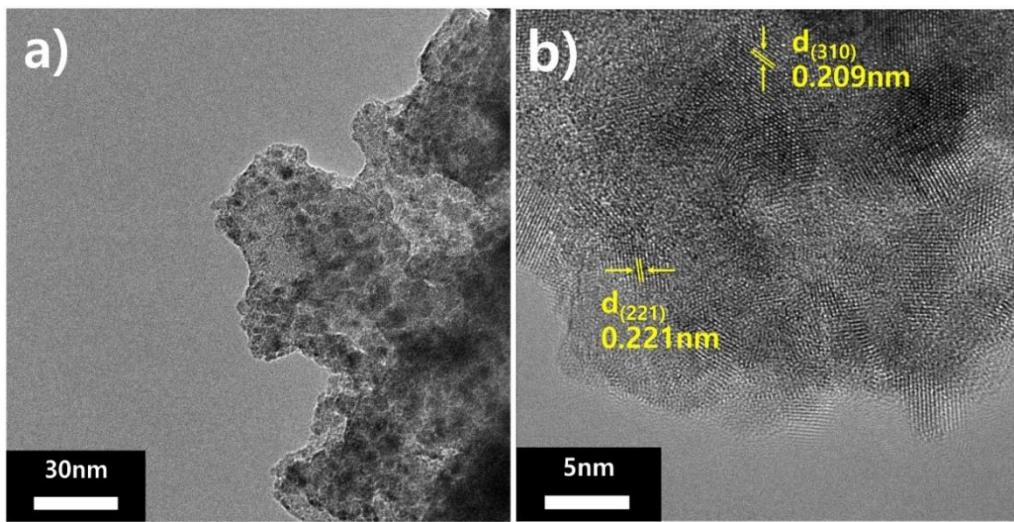


Fig. S10. TEM images of $\text{Ni}_2\text{Mo}_3\text{N}/\text{NF}$ after durability tests.

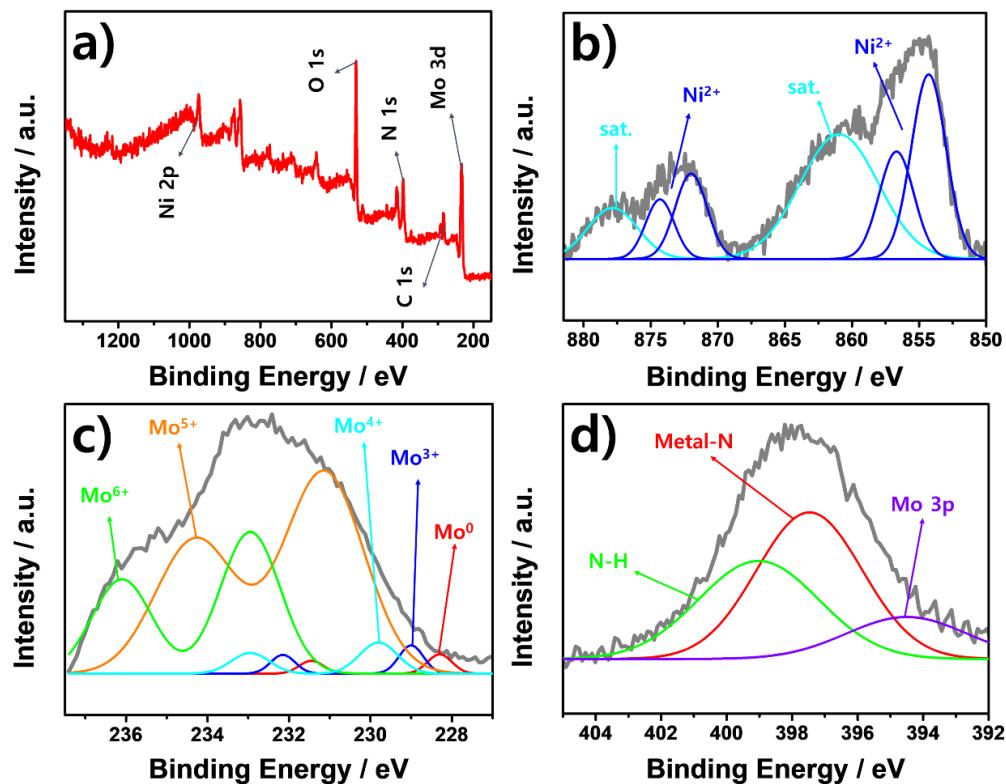


Fig. S11. XPS spectra of $\text{Ni}_2\text{Mo}_3\text{N}/\text{NF}$ after durability tests for a) survey, b) Ni 2p, c) Mo 3d, and d) N 1s.

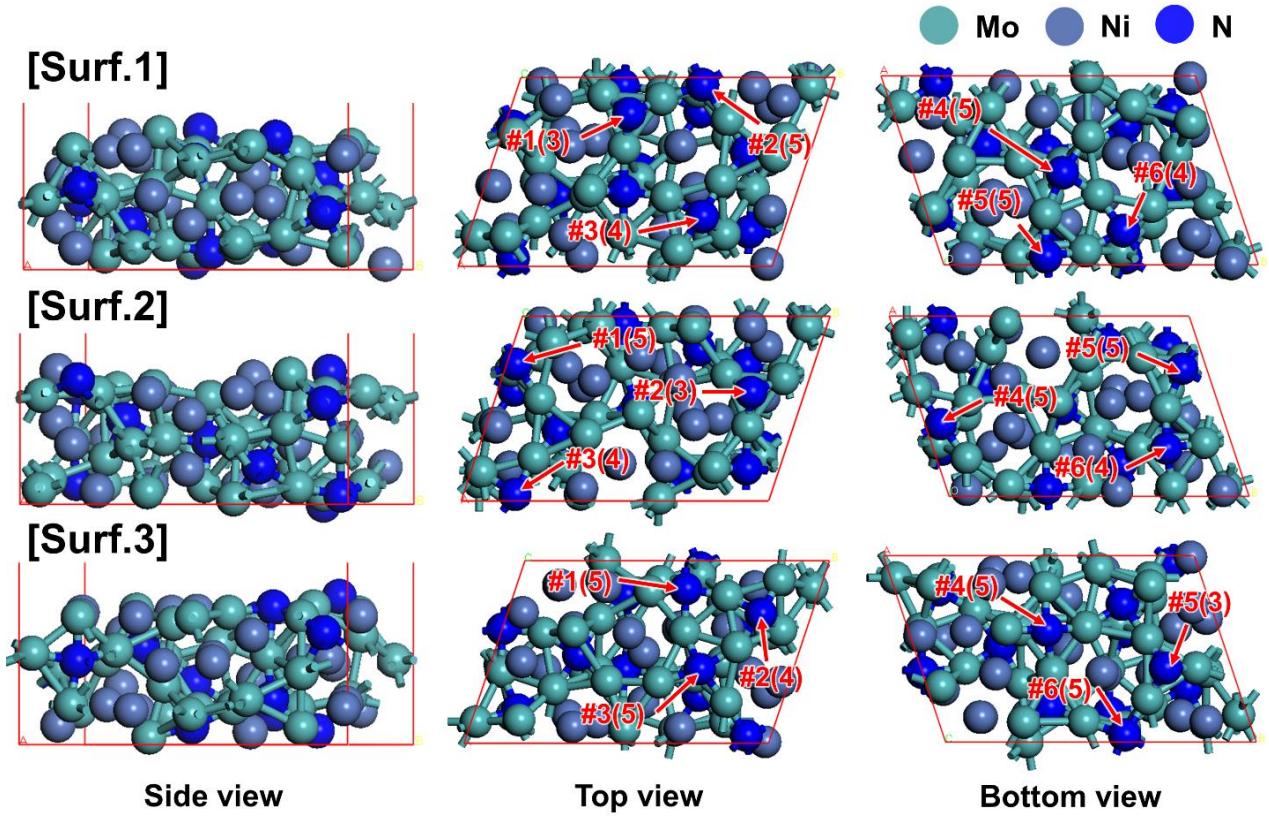


Fig. S12. The atomic structure of stoichiometric surface models which parallel to the (221) surface.

Possible nitrogen active sites are indicated with a red arrow, and the numbers in parenthesis denote coordination number counting the N-Mo bonding.

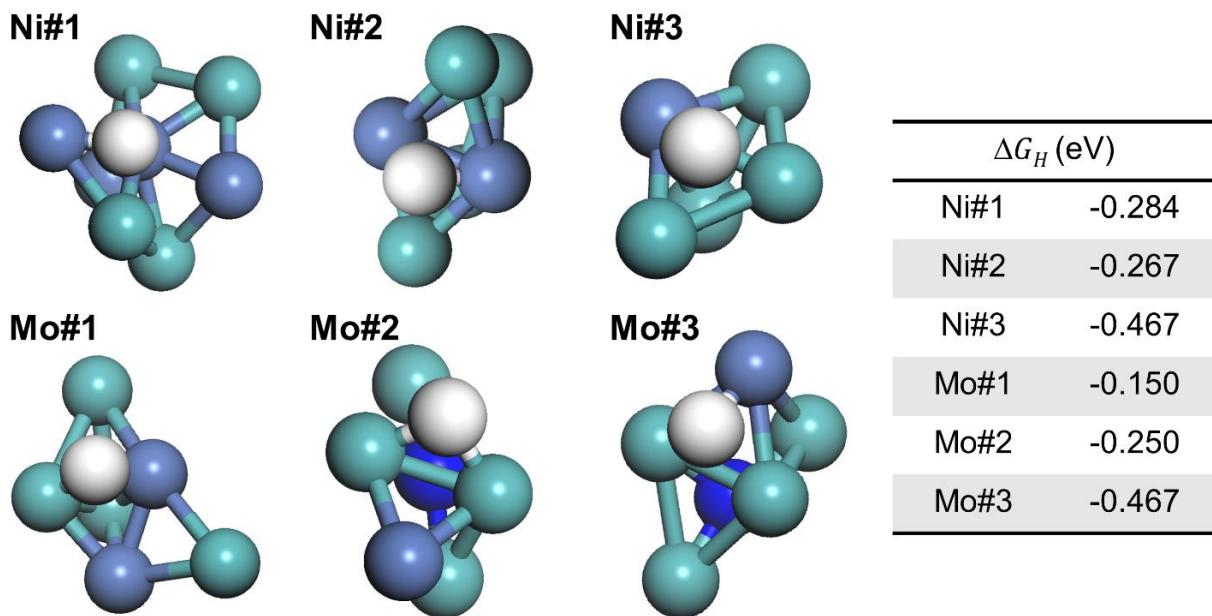


Fig. S13. H-adsorption structures and energies for Ni and Mo sites on the surface of Surf.1 in Figure S12. Light blue, turquoise, blue, and white spheres represent Ni, Mo, N, and H atoms, respectively.

Table S1. Comparison of the HER performance in alkaline media with reported state-of-the-art

TMN-based catalysts.

Catalyst	η_{10} (mV)	η_{100} (mV)	Tafel slope (mV dec ⁻¹)	Reference
Ni₂Mo₃N/NF	21.3	123.8	62	This work
V-Ni₂Mo₃N	54	117	42.8	1
V-Ni_{0.2}Mo_{0.8}N	39	178 (200 mA cm ⁻²)	37.7	2
NiMoN-NF700	38	118 (50 mA cm ⁻²)	46	3
FeNi₃N/NG	98 (20 mA cm ⁻²)	186	83.1	4
Co-NiMoN-400 NRs	45		72.2	5
Ni@NCNT/NiMoN-8	15	156 (50 mA cm ⁻²)	68	6
Ni-Mo-N/NG	46.6	159.8	45	7
Ni-Fe-MoN NTs	55	199	109	8
NiMoN-550	89	≥260	79	9
NiMoN	109	≥180	95	10
MoVN	108	≥175	60	11
NSP-Co₃FeNx	23	147	94	12
Co₂Ni₁N	102.6	≥200 (50 mA cm ⁻²)	60.2	13
Mo₂(CN)_{0.5}	80	202	40	14
Co-Mo₂N@NC	47	170	43	15
Mo₂N/NC-2	217	≥410	115.7	16
h-MoN@BNCNT	78		46	17
CoN-400/CC	97	≥200	93.9	18
Mo-600	85		54	19
S-2-T5	76	240	47	20

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